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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/550,591	09/13/2006	Dong-seok Kim	29137.096.00	1374
30827	7590	03/11/2009	EXAMINER	
MCKENNA LONG & ALDRIDGE LLP 1900 K STREET, NW WASHINGTON, DC 20006			LISTVOYB, GREGORY	
ART UNIT	PAPER NUMBER			
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03/11/2009	PAPER			

Please find below and/or attached an Office communication concerning this application or proceeding.

The time period for reply, if any, is set in the attached communication.

Office Action Summary	Application No. 10/550,591	Applicant(s) KIM ET AL.
	Examiner GREGORY LISTVOYB	Art Unit 1796

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --
Period for Reply

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) OR THIRTY (30) DAYS, WHICHEVER IS LONGER, FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
 - If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
 - Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED. (35 U.S.C. § 133).
- Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

Status

- 1) Responsive to communication(s) filed on **21 January 2009**.
 2a) This action is FINAL. 2b) This action is non-final.
 3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

Disposition of Claims

- 4) Claim(s) **1 and 3-17** is/are pending in the application.
 4a) Of the above claim(s) **4-17** is/are withdrawn from consideration.
 5) Claim(s) _____ is/are allowed.
 6) Claim(s) **1 and 3** is/are rejected.
 7) Claim(s) _____ is/are objected to.
 8) Claim(s) _____ are subject to restriction and/or election requirement.

Application Papers

- 9) The specification is objected to by the Examiner.
 10) The drawing(s) filed on _____ is/are: a) accepted or b) objected to by the Examiner.
 Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).
 Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).
 11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.

Priority under 35 U.S.C. § 119

- 12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
 a) All b) Some * c) None of:
 1. Certified copies of the priority documents have been received.
 2. Certified copies of the priority documents have been received in Application No. _____.
 3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).

* See the attached detailed Office action for a list of the certified copies not received.

Attachment(s)

- | | |
|---|---|
| 1) <input checked="" type="checkbox"/> Notice of References Cited (PTO-892) | 4) <input type="checkbox"/> Interview Summary (PTO-413)
Paper No(s)/Mail Date: _____ |
| 2) <input type="checkbox"/> Notice of Draftsperson's Patent Drawing Review (PTO-948) | 5) <input type="checkbox"/> Notice of Informal Patent Application |
| 3) <input type="checkbox"/> Information Disclosure Statement(s) (PTO/US/06)
Paper No(s)/Mail Date: _____ | 6) <input type="checkbox"/> Other: _____ |

DETAILED ACTION

Continued Examination Under 37 CFR 1.114

A request for continued examination under 37 CFR 1.114, including the fee set forth in 37 CFR 1.17(e), was filed in this application after final rejection. Since this application is eligible for continued examination under 37 CFR 1.114, and the fee set forth in 37 CFR 1.17(e) has been timely paid, the finality of the previous Office action has been withdrawn pursuant to 37 CFR 1.114. Applicant's submission filed on 1/21/2009 has been entered.

Claim Rejections - 35 USC § 103

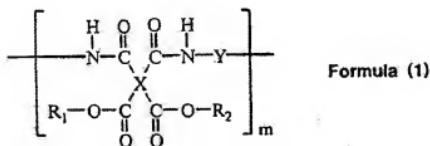
The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negated by the manner in which the invention was made.

Claims 1, 3 rejected under 35 U.S.C. 103(a) as being unpatentable over Jung et al (US 2002/0093077) herein Jung in view of Okada et al (US 2002/0055610) herein Okada and evidenced by Hosaka et al (US 2004/0048004) herein Hosaka and further in view of Maeda et al (US 6664021) herein Maeda or Machida et al (US 6159654) herein Machida (necessitated by Amendment).

Jung discloses a reactive transparent polyimide precursor having the structure of

the following Formula (1) (see Claim 1):



Where

R₁ and R₂ are independently a Hydrogen atom, or an acid-dissociable group, which may contain an unsaturated Hydrocarbon C 1-20 (see Claim 6).

X is a tetravalent, an aromatic or an aliphatic organic group; Y is a divalent, an aromatic or an aliphatic organic group; and m is an integer equal to or greater than 1.

Jung discloses that the ratio between Hydrogen atom and acid-dissociable group is within the broad range of 0.1-1 (see Claim 7), which gives the acid value of the precursor within the range of 30 to 200 mg KOH/g.

Note that claim 1 of Application examined claims R₁ and R₂ (which correspond with R₁ and R₂ of Jung) are independently each other hydrogen atom, or organic groups ...provided that they are not hydrogen atoms at the same time.

Therefore, acidic group constitutes 0.5-1 ratio to Hydrogen. In other words the minimum ratio of substituted groups to Hydrogen is 0.5.

Thus, the above amount is within the ratio disclosed by Jung.

Jung does not teach that "X" is alicyclic tetracarboxylic acid and molecular weight of his polyimide precursor and that fragment Y has an ethylenically unsaturated bonds.

Okada discloses a reactive transparent polyimide precursor and polyimide comprising a reaction product of alicyclic tetracarboxylic acid dianhydride (1,2,3,4 cyclobutanetetracarboxylic acid dianhydride, (see line 0139)- the same compound used in the Application) and diamine, having ethylenically unsaturated side chain (the same diamines used in the application, see line 0150).

Okada clearly teaches that the above diamines have photosensitive groups, which means that they can be successfully used in photosensitive polyimides.

Since Jung discloses such a composition, diamine, containing ethylenically unsaturated groups increases polyimide response to radiation, which makes the following cross-linking more efficient.

Therefore, it would have been obvious to a person of ordinary skills in the art to use diamine having ethylenically unsaturated side chains for production of a photosensitive polyimide precursor, since their presence increase polyimide response to radiation, which makes the following cross-linking more efficient.

As evidenced by Hosaka, alicyclic tetracarboxylic acid is preferred in optical applications due to its excellent transparency (see line 0043).

Therefore, it would have been obvious to a person of ordinary skills in the art at the time the invention was made to use alicyclic tetracarboxylic acid component in Jung's polyimide precursor to obtain film with excellent transparency

In reference to Claim 3, Okada teaches that Molecular Weight of the polyamide precursor is within the range of 5000-1000000 (see line 0136).

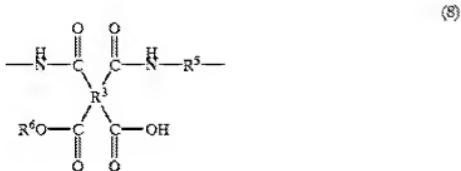
If the average molecular weight is less than 5,000, the resulting soluble polyimide will have a smaller molecular weight. Accordingly, the photosensitive resin composition including such soluble polyimide, if used as it is, is not practical because of its brittleness. Conversely, if the polyamic acid has an average molecular weight of greater than 1,000,000, a varnish of the polyamic acid will have an excessively high viscosity, so that the handling thereof will be difficult. (see line 0108).

Therefore, it would have been obvious to a person of ordinary skills in the art at the time the invention was made to prepare polyimide precursor with molecular weight within the range of 5000-1000000.

Regarding new limitation of claim 1, Jung does not teach his polyimide being negative polyimide precursor.

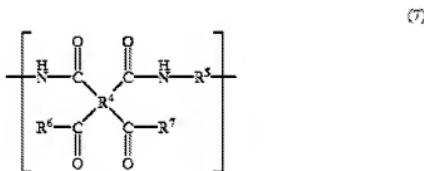
Machida and Maeda teach negative polyimide precursor.

Maeda teaches negative polyimide precursor composition (see Abstract, Column 1, line e15, having a following formula:



where R3 is alicyclic group and R6 is C1-C7 alkyl.

Machida teaches negative photosensitive polymer composition (see Abstract), comprising the following structure (see Column 12, line 55) :



wherein R⁴ is a quadrivalent organic group; R⁵ is a bivalent organic group; R⁶ and R⁷ may be the same or different and are individually a monovalent organic group or hydroxyl group with a proviso that at least one of R⁶ and R⁷ is an organic group having a hydroxyl group bonded directly to an aromatic ring.

Maeda teaches that his negative type photosensitive resin composition having excellent sensitivity and resolving properties which can inhibit volume shrinkage at the

time of curing, can suitably adhere to a substrate, and can form a polyimide coating film pattern having good heat resistance on the substrate by baking (see Column 1, line 10).

Note that Jung polyimide is analogous to one disclosed by Maeda and Machida. Therefore, Jung's polyimide possesses properties analogous to ones of Maeda.

Thus , it would have been obvious to a person of ordinary skills in the art to apply Jung's polyimide, modified with Okada, Machida or Maeda as a negative type precursor, since it possesses excellent sensitivity and resolving properties which can inhibit volume shrinkage at the time of curing, can suitably adhere to a substrate, and can form a polyimide coating film pattern having good heat resistance on the substrate by baking.

Response to Arguments

Applicant's arguments with respect to claims 1 and 3 have been considered but are moot in view of the new ground(s) of rejection.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to GREGORY LISTVOYB whose telephone number is (571)272-6105. The examiner can normally be reached on 10am-7pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, James Seidleck can be reached on (571) 272-1078. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

/Rabon Sergent/
Primary Examiner, Art Unit 1796

GL